

SHIGA7.036APC

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Masuda et al.
Appl. No.	:	Unknown
Filed	:	Herewith
For	:	POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Unknown
Group Art Unit	:	Unknown

**PRELIMINARY AMENDMENT**

**Mail Stop Amendment**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 3 of this paper.

**Remarks/Arguments** begin on page 5 of this paper.